

tips, they can exert very high local pressures on the surface. This “rolling grain” model forms the physical basis of the wire sawing process. Similar surface structures also form after lapping semiconductor surfaces with loose abrasive particles.

The individual process of the interaction of a single particle with sharp edges and the surface of a brittle material can be studied by micro-indentation experiments. This is shown in Figure 6.17(b) for a silicon surface. The damage structure of several overlapping micro-indentations with a Vickers diamond indenter resembles the structure of an as-cut wafer. Numerous micro-indentation experiments on monocrystalline silicon have been carried out in the past to investigate the damage structure quantitatively (e.g. [33–37]). The main results are summarised schematically in Figure 6.18 for a “sharp” Vickers indenter with pyramid geometry. Loading by sharp indenters first leads to the generation of a remnant plastic impression in the surface known as the elastic–plastic zone. Recent Raman investigations of this region have shown that under high pressures the silicon lattice transforms into other crystal structures. Several phase changes have been observed directly under the indenter, in particular a metallic high-pressure phase [38, 39]. Under loading at 11.8 GPa an endothermic transformation to metallic silicon (Si II) occurs ($\Delta G = 38$ kJ/mol), which partly transforms back to another high-pressure phase (Si III at 9 GPa, $\Delta G = -8.3$ kJ/mol). In the metallic state the silicon can plastically deform and

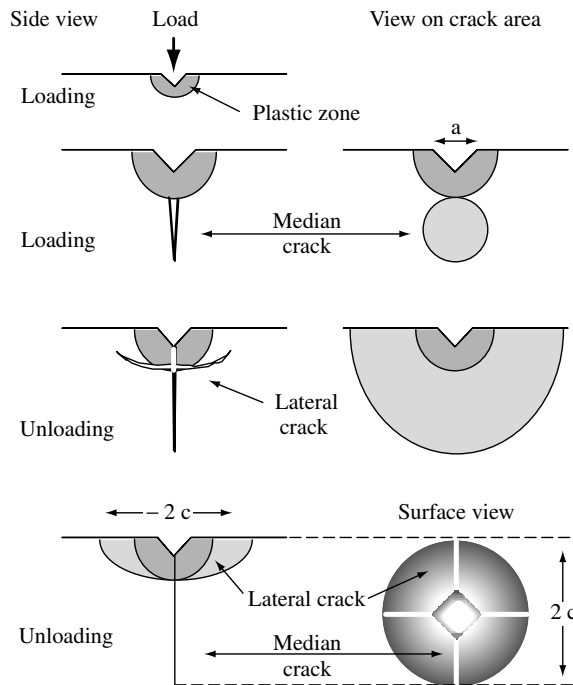


Figure 6.18 Schematic diagram of the development of the crack system below a sharp indenter upon loading and unloading. Dark gray areas indicate the plastic zone below the indenter. The dotted areas are the crack planes of the halfpenny-shaped median crack system. They are viewed from end-on (left side) or perpendicular to the plane (right side). In case radial cracks also occur, they may coalesce with the median crack and form a similar crack pattern